

Chain Magnetron Sputter System

Model: SA-VKI2000

SA-VKI2000 is an inline production-grade magnetron sputtering system. It provides a large coating area, stable operation, a highly automated control system and low-maintenance design, satisfying mass-production requirements for sputter coating of large-size workpieces.



Feature

- High thin-film purity
- Excellent substrate adhesion
- Relatively high ionization rate
- Co-sputtering with mixed targets

Application

- Laser
- R&D
- Integrated circuit
- MEMS

Specifications:

Parameter	Descriptions
Number of Cathodes	2(max.)
Sputtering Power Supply	DC / RF / pulsed DC, freely switchable
Ion Source	Anode & Kaufman & RF ion source
Bias	RF / pulsed DC
Vacuum Sampling Chamber	Fully-automatic sampling chamber, optional
Pumping System	Cryopump / magnetically levitated turbo-molecular pump + Dry mechanical pump
Flow Control	Digital mass flow meter
Coating Uniformity	±3%
Coating Repeatability	±2%
Uniform Deposition Area	1000 mm×1000 mm(max.)
Ultimate Vacuum	3E-5Pa
Vacuum Measurement	Full-range vacuum gauge + Capacitance diaphragm gauge
Temperature Control Range	RT~300℃
Space Requirements(L×W×H,m)	5×2.8×1.6

Principle:

